

WHAT IS CLAIMED IS:

1. A thin-film deposition device comprising:
a vacuum chamber;
a substrate holder provided in the vacuum chamber; and
at least one tubular gas supply end that supplies gas
towards a substrate mounting-face on the substrate holder,
wherein the gas supply end includes therein barriers
that control the gas flow in the gas supply end and that are
disposed at predetermined intervals toward a gas supply port
of the gas supply end, each of the barriers having a
plurality of apertures.

2. The thin-film deposition device according to Claim
1, wherein the barriers that are disposed closer to the gas
supply port have a larger number of apertures each having
smaller opening spaces.

3. The thin-film deposition device according to Claim
1, wherein said at least one tubular gas supply end
comprises a plurality of gas supply ends.

4. The thin-film deposition device according to Claim
1, wherein the gas supply end is connected with a plurality
of gas supply tubes that introduce gas into the gas supply

end.

5. The thin-film deposition device according to Claim 1, wherein the gas supply end has a structure such that gas is supplied in a collimated fashion to a long rectangular area on the substrate mounting-face across the width thereof.

6. The thin-film deposition device according to Claim 5, wherein the substrate holder includes a sliding mechanism that moves the substrate mounting-face parallel to the short axis of the long rectangular area to which the gas is supplied.

7. The thin-film deposition device according to Claim 1, wherein the gas supply end has a structure such that gas is supplied to the entire surface of a substrate mounted on the substrate mounting-face.